

[Home](#) | [Index](#) | [Resources](#) | [Contact](#) | [Privacy](#) | [About](#)**Scientific and Technical Information Center****NPL Virtual Library > Request a Prior Art Search**[Patents Home](#) | [Site Feedback](#)[NPL Home](#) | [STIC Catalog](#) | [Site Guide](#) | [EIC](#) | [Automation Training/ITRPs](#) | [Contact Us](#) | [STIC Staff](#) | [FAQ](#) | [Firewall Authentication](#)**Commercial Database Search Request**

Search requests relating to published applications, patent families, and litigation may be submitted by filling out this form and clicking on "Send."

For all other search requests, fill out the form, print, and submit the printout with any attachments to the STIC facility serving your Technology Center.

**Tech Center:**

- ☐ TC 1600   ☒ TC 1700   ☐ TC 2100   ☐ TC 2600  
☐ TC 2800   ☐ TC 3600   ☐ TC 3700   ☐ Other

**Enter your Contact Information below:**

Name:

LYNETTE T. UMEZ-ERONINI

Employee Number: 74987

Phone:

306-9074

Art Unit or Office: 1765

Building &amp; Room Number:

CP3-10E12

Enter the case serial number (Required): 09891730

If not related to a patent application, please enter NA here.

Class / Subclass(es) 438/745

Earliest Priority Filing Date: 6/26/2000

**Format preferred for results:**☒ Paper   ☐ Diskette   ☐ E-mail**Provide detailed information on your search topic:**

- In your own words, describe in detail the concepts or subjects you want us to search.
- Include synonyms, keywords, and acronyms. Define terms that have special meanings.
- **\*For Chemical Structure Searches Only\***  
Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers

- **\*For Sequence Searches Only\***  
Include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.
- **\*For Foreign Patent Family Searches Only\***  
Include the country name and patent number.
- Provide examples or give us relevant citations, authors, etc., if known.
- FAX or send the **abstract, pertinent claims** (not all of the claims), **drawings, or chemical structures** to your EIC or branch library.

**Enter your Search Topic Information below:**

INVENTOR-Verhaverbeke, Steven and Truman, J. Kelly

**ABSTRACT:**

The present invention is a novel cleaning method and a solution for use in a single wafer cleaning process. According to the present invention the cleaning solution comprises ammonium hydroxide (NH.sub.4OH), hydrogen peroxide (H.sub.2O.sub.2), water (H.sub.2O) and a chelating agent. In an embodiment of the present invention the cleaning solution also contains a surfactant. And still yet another embodiment of the present invention the cleaning solution also comprises a dissolved gas such as H.sub.2. In a particular embodiment of the present invention, this solution is used by spraying or dispensing it on a spinning wafer.

SEARCH: claims 20 and 21 for "polyoxyethylene butylphenyl ether" and "polyoxyethylene alkylphenyl sulfate" in "cleaning" a "wafer" or "semiconductor"

1. A method of processing a wafer comprising: placing a wafer in a single wafer cleaning tool; spinning said wafer in said single wafer cleaning tool and while spinning said wafer; after placing said wafer in said single wafer cleaning tool, exposing said wafer to a solution comprising: NH.sub.4OH; H.sub.2O; and a chelating agent.

15. The method of claim 1 wherein said solution is further comprises a surfactant.

**Special Instructions and Other Comments:**

(For fastest service, let us know the best times to contact you, in case the searcher needs further clarification on your search.)

Press ALT + F, then P to print this screen for your own information.

SEND

RESET

USPTO [Intranet Home](#) | [Index](#) | [What's New](#) | [Resources](#) | [Contacts](#) | [Internet](#) | [Search](#) | [Firewall](#) | [Web Services](#)

Last Modified: Thursday, July 24, 2003 15:31:52